

Search Notes



Application/Control No.

10/617 682

Examiner

D. Rutledge

**Applicant(s)/Patent under
Reexamination**

AKUTSU ET AL.

Art Unit

2851

SEARCHED

SEARCH NOTES (INCLUDING SEARCH STRATEGY)

TERM	DEFINITION	DATE	EXMR
electron adj beam, plural\$3 or multiple; (wafer or substrate); stage or table; interferomet\$3 or measur\$5;		3/25/2005	DR
position or location or align\$4; rotating or rotation\$2; direction; z adj axis; measuring adj (light or beam) near4		3/25/2005	DR
perpendicular near4 electron adj beam		3/25/2005	DR

INTERFERENCE SEARCHED

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
355	53,67,75	3/25/2005	DR
250	491.1	3/25/2005	DR
250	492.2	3/25/2005	DR
310	10, 12	3/25/2005	DR